



SHEET 1 OF 2

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 055071-0310		SERIAL NO. 10/705,234	
				APPLICANT Armin LIEBCHEN			
				FILING DATE November 12, 2003		GROUP 2851	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code2 (if known)		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
<i>PK</i>			5,969,441	10/19/1999	Loopstra et al.		
<i>PK</i>		US	6,046,792	04/04/2000	Van Der Werf et al.		
<i>PK</i>		US	6,563,566 B2	05/13/2003	Rosenbluth et al.		
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FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number 4-Kind Codes (if known)		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No
<i>PK</i>		WO 98/40791		09/17/1998	Konin Klijke Philips Electronics N.V.		
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
EXAMINER <i>PK</i>				DATE CONSIDERED <i>9/13/05</i>			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered.
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1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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PIL ↓ PK		US	5,680,588	10-21-1997	Gortych et al.			
		US	5,300,786	04-05-1994	Brunner et al.			
		US	5,805,290	09-08-1998	Ausschnitt et al.			
		US	5,965,309	10-12-1999	Ausschnitt et al.			
		US	5,680,588	10-21-1997	Gortych et al.			
		US	6,033,814	03-07-2000	Burdorf et al.			
		US	6,128,067	10-03-2000	Hashimoto			
		US						
		US						
		US						
		US						
		US						
FOREIGN PATENT DOCUMENTS								
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number + Kind Codes (# known)		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No	
PIL		JP 2000-232057A					X	
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.						
PIL		BURN J. LIN, "The Exposure-Defocus Forest," Jpn. J. Appl. Phys. Vol. 33 (1994) pp 6756-6764						
↓		M. DUSA et al., "Study of mask aerial images to predict CD proximity and line end shortening of resist patterns," Proc. of SPIE Vol. 4349 (2001), pp. 148-159						
↓		B.P. MATHUR et al., "Quantitative Evaluation of Shape of Image on Photoresist of Square Apertures," IEEE Transactions of Electron Devices, Vol. 35, No. 3 (March 1988), pp. 294-297						
↓		CHRISTOPHER J. PROGLER et al., "Merit functions for lithographic lens design," J. Vac. Sci. Technol. B 14(6), (Nov/Dec 1996), pp. 3714-3718						
PK		NISHRIN KACHWALA et al., "Imaging contrast improvement for 160 nm line features using sub resolution assist features with binary, 6% ternary attenuated phase shift mask with process tuned resist," SPIE Vol. 3679 (1999), pp. 55-67						
EXAMINER Pete R. King				DATE CONSIDERED 9/13/05				

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